



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application No.: 10/669,623  
Applicants: Christian DUSSARRAT, et al.  
Filed: September 24, 2003  
Title: METHODS FOR PRODUCING SILICON NITRIDE FILMS  
AND SILICON OXYNITRIDE FILMS BY THERMAL  
CHEMICAL VAPOR DEPOSITION  
TC/A.U.: 1762  
Examiner: Bret P. Chen  
Docket No.: Serie 5444  
Customer No.: 000040582

**AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Office Action of December 9, 2005, please amend the application as follows:

**Amendments to the Specification** begins on page 2 of this paper.

**Amendments to the Claims** are reflected in the listing of claims which  
begin on page 4 of this paper.

**Remarks** begin on page 13 of this paper.